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Class	Subclass
ISSUE CLASSIFICATION	

PATENT NUMBER

U.S. UTILITY Patent Application

O.I.P.E. <i>FA</i> SCANNED <i>A.G. 3</i> on <i>10/3</i>	PATENT DATE
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APPLICATION NO. 09/882141	CONT/PRIOR D	CLASS 136 454	SUBCLASS 700	ART UNIT 1765	EXAMINER Wm. K. H. Jones
APPLICANTS Yijiong Wang Maicheng Li Shaojun Pan					
TITLE Method of etching high aspect ratio openings in silicon					

PTO 436A
 1299

ISSUING CLASSIFICATION

ORIGINAL		CROSS REFERENCE(S)			
CLASS	SUBCLASS	CLASS	SUBCLASS (ONE SUBCLASS PER BLOCK)		
ATTORNEY'S CLASSIFICATION					

☐ Continued in Serial No. 1000, filed 10/18/81

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	(Assistant Examiner) (Date)			NOTICE OF ALLOWANCE MAILED	
	(Priority Examiner) (Date)			ISSUE FEE Amount Paid	
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